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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/987,990	11/16/2001	Tsutomu Shoki	Q67319	8044

7590 07/15/2003

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[REDACTED] EXAMINER

ROSASCO, STEPHEN D

[REDACTED] ART UNIT [REDACTED] PAPER NUMBER

1756

DATE MAILED: 07/15/2003

b

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)
	09/987,990	SHOKI ET AL.
	Examiner Stephen Rosasco	Art Unit 1756

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on 26 February 2002.
- 2a) This action is FINAL. 2b) This action is non-final.
- 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 1-15 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) Claim(s) _____ is/are allowed.
- 6) Claim(s) 1-15 is/are rejected.
- 7) Claim(s) _____ is/are objected to.
- 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
- 10) The drawing(s) filed on 16 November 2001 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- 11) The proposed drawing correction filed on _____ is: a) approved b) disapproved by the Examiner.
 If approved, corrected drawings are required in reply to this Office action.
- 12) The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

- 13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) All b) Some * c) None of:
1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- * See the attached detailed Office action for a list of the certified copies not received.
- 14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
 a) The translation of the foreign language provisional application has been received.
- 15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

- | | |
|---|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) Paper No(s). _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO-1449) Paper No(s) 5 . | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

The disclosure is objected to because of the following informalities: there are numerous spelling and grammatical errors present, e.g., page 3, Summary of Invention line 2, "object of this invention a substrate"; page 15, paragraph 5, "and is baked at 200", last paragraph, line 2, "temperature of 20" ... Further the resist, which is, remained"; page 18, second paragraph, "(0.14. m); page 19, last line and page 20 last paragraph, the unit designations are not complete.

Appropriate correction is required.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 1-15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tong et al. (6,352,803).

The claimed invention is directed to a reflection mask blank, a reflection mask and a method of making said mask for EUV exposure, comprising: a substrate; a multilayer film which is formed on the substrate so as to reflect an EUV light ray; and a light absorber layer which is formed on the multilayer film so as to absorb the EUV light ray, wherein the multilayer film has flatness with respect to a surface thereof, and the flatness is 100 nm or less.

Tong et al. teach a transparent EUVL mask substrate, comprising: a substrate composed of low thermal expansion material, a first layer of silicon on a frontside of said

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substrate, a multilayer structure on said first layer of silicon, a second layer of silicon on a backside of said substrate, and a layer of conductive material on said second layer of silicon.

And additionally including a film of stress balancing material between the frontside of said substrate and said first layer of silicon. And wherein said low thermal, wherein said stress balancing material is a film consisting of TaSi.

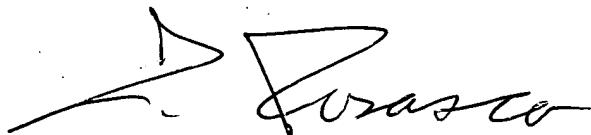
The teachings of Tong et al. differ from those of the applicant in that the applicant teaches a specific flatness to the multilayer film of 100 nm or less.

However, Tong et al. also teach (col. 2, lines 5-9) that an EUVL mask demands low flatness error and low roughness to minimize the image placement error and loss of reflectivity, respectively; and that any method to help achieve the flatness and roughness requirements is desirable.

Therefore, it would have been obvious to one having ordinary skill in the art to take the teachings of Tong et al. and employ any method to ensure that the surface flatness that is needed is achieved in order to make the claimed invention because this is understood to be a necessary requirement by those skilled in the art.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to S. Rosasco whose telephone number is (703) 308-4402.

Any inquiry of a general nature or relating to the status of this application should be directed to the Group receptionist whose telephone number is (703) 308-0661. Fax (703) 872-9310 Before Finals; 872-9311 After Finals.



S. Rosasco
Primary Examiner
Art Unit 1756

S.Rosasco
7/10/03